

IN THE SPECIFICATION:

Page 1, paragraph [0001].

The present application is a divisional of U.S. Patent Application No. 09/976,681 filed on October 12, 2001 entitled "Template Design for Room Temperature, Low Pressure Micro- and Nanoimprint Lithography," which claims priority to U.S. Provisional Patent Application No. 60/239,808 filed on October 12, 2000 entitled "Template Design for Room Temperature, Low Pressure Micro- and Nanoimprint Lithography and Method for Sensing Gap or Film Thickness," and is a divisional of U.S. Patent Application No. 09/907,512 filed on July 16, 2001 entitled "High-Resolution Overlay Alignment Methods and System for Imprint Lithography," which claims priority to U.S. Provisional Patent Application No. 60/218,568 filed on July 16, 2000 entitled "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," both all of which are incorporated by reference herein.

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